# Introduction into ESD Challenges

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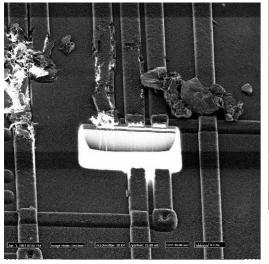
#### **Present Concepts and Accepted Assumptions**

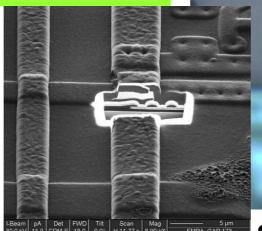
- ESD is generally known as a problem of capsulated devices if they are handled incorrectly: Touching by elektrostatically charged persons, non-ESD-safe mailing etc. generates high-voltage pulse introduction into device pins
- Therefore, device pins are protected against ESD by special protection structures.
- Using standardized ESD tests, based on generally accepted models (human-body-model, chargeddevice-model, machine-model) the chips should be tested on their ESD-robustness, which is basically limited by the quality and area of their pinprotective structures.
- ESD influence by operators should be avoided by suitable protection concepts (floor, shoes, hand discharge setup etc.)

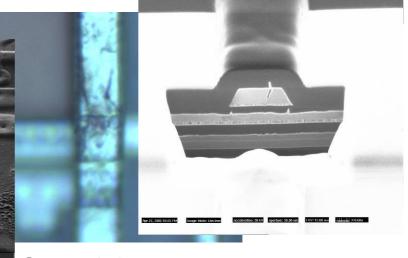
### Considerations

- ESDFOS (Electrostatic Discharge From Outside to Surface)-related failures are often mixed up with mechanical damage
- No specific ESDFOS examinations related to copper metallizations have been done, yet
- We punish non ESD-conformal behaviour of line staff, but still accept kV's of device surface charging by tool robotics !!!???

#### **ESDFOS History**

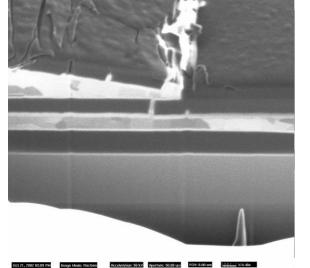


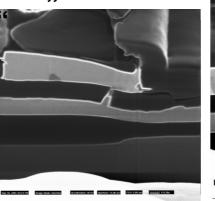


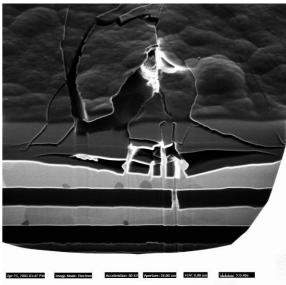


Such failures were proven as typical ESDFOS failures

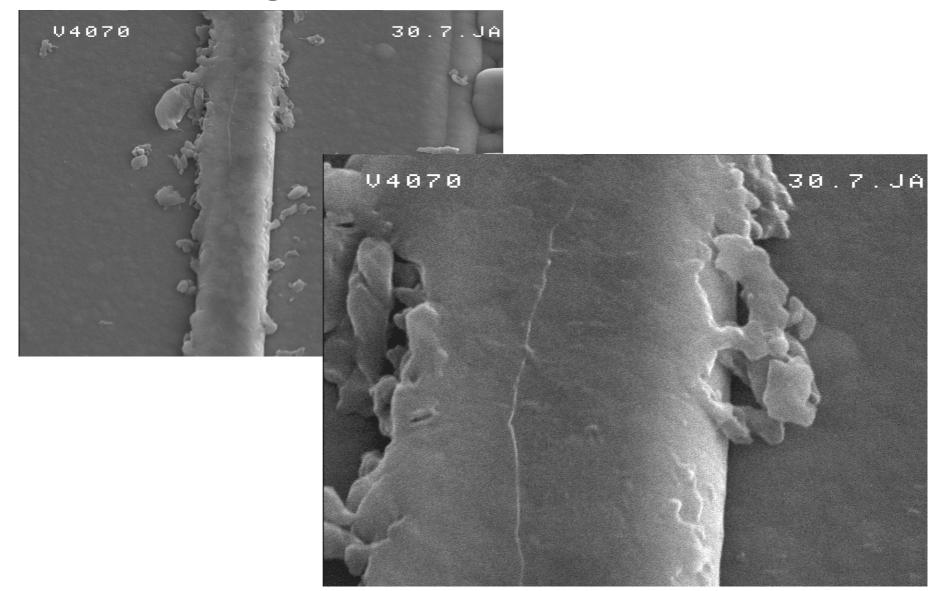
Often they have been wrongly taken into the category of "mechanical damage"



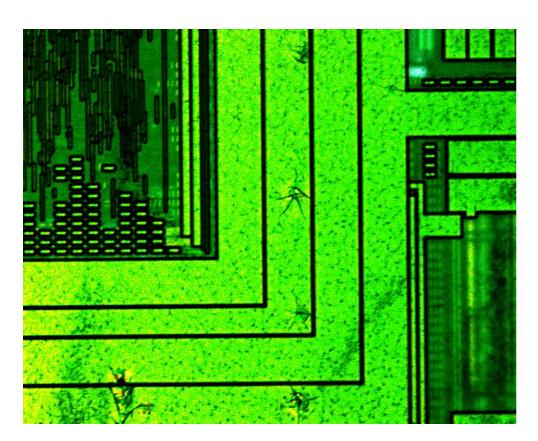




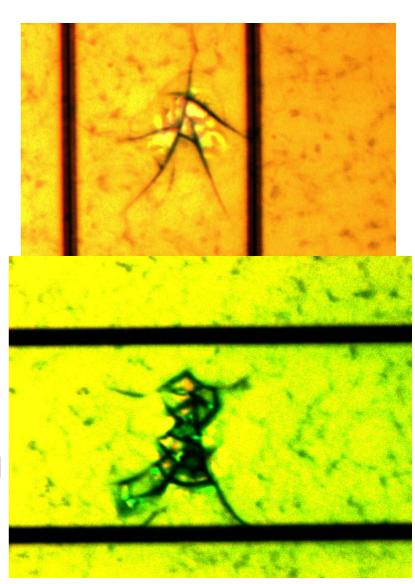
# Crack length and SEM appearance



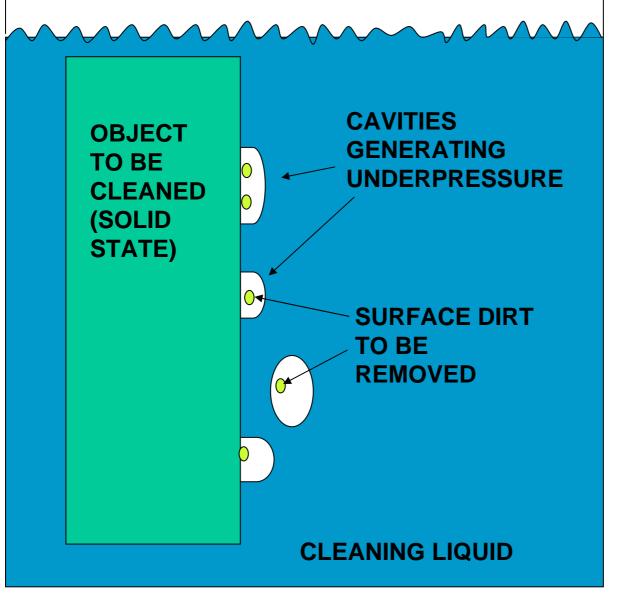
### ESDFOS by ultrasonic cleaning



This example shows US-cleaning-induced ESDFOS, using some days old DI-water. After replacing the water by new DI water, the effect disappeared.

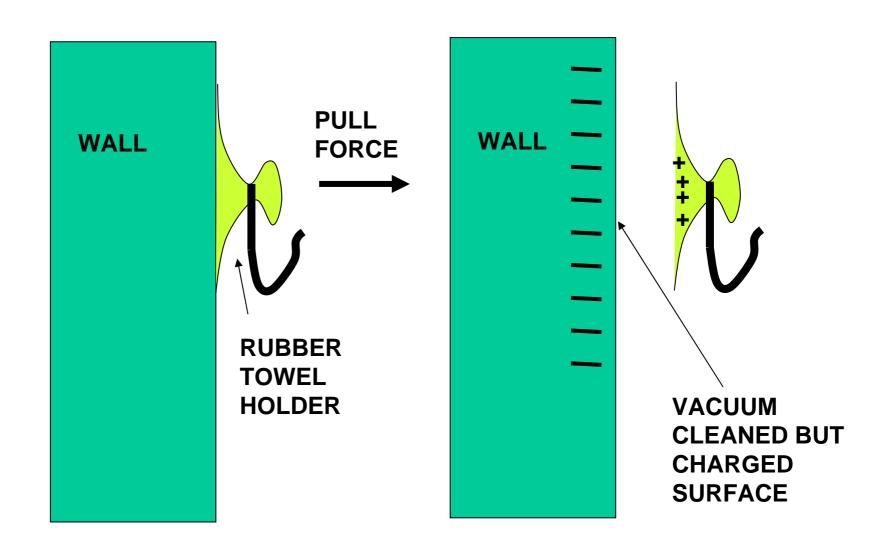


#### **Ultrasonic Cleaning Principle by Cavities**

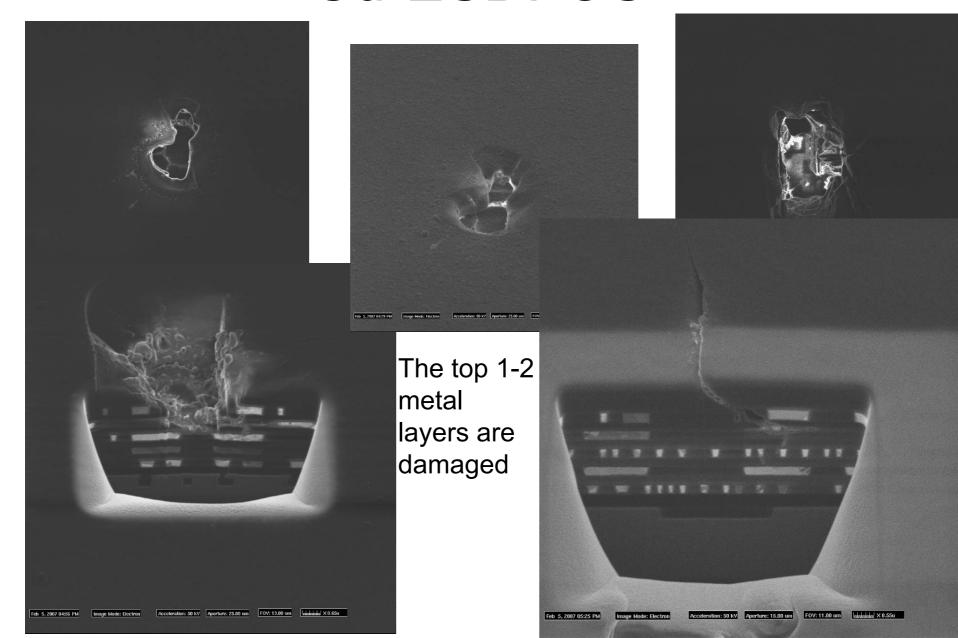


**Ultrasonic** bath, frequency approximately 42 kHz, often using isolating cleaning liquids

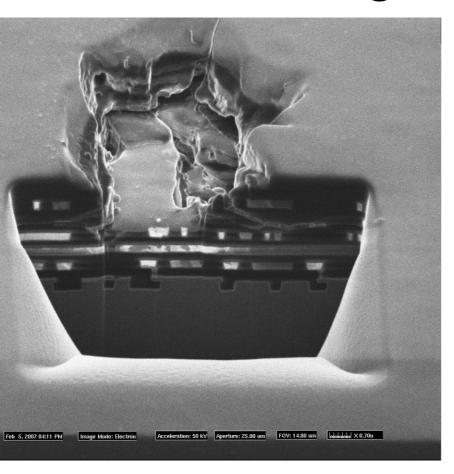
#### Model for Cavity Ultrasonic Cleaning Effect

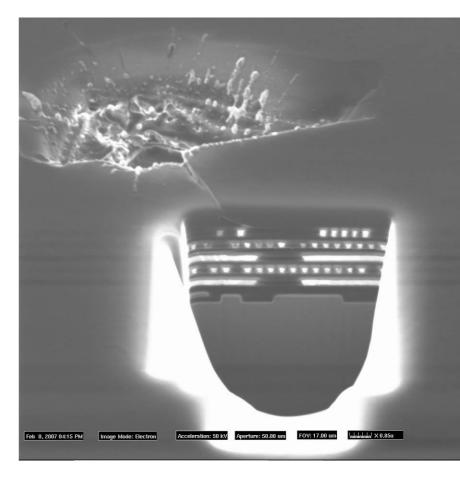


### Cu-ESDFOS



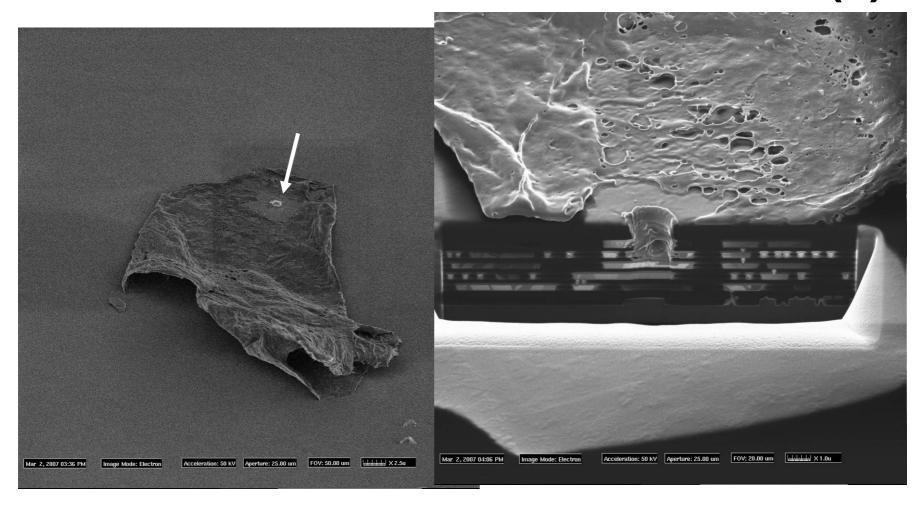
### Cu: High Severeness





Damage into deep metal layers, cracking interlevel dielectrics inbetween

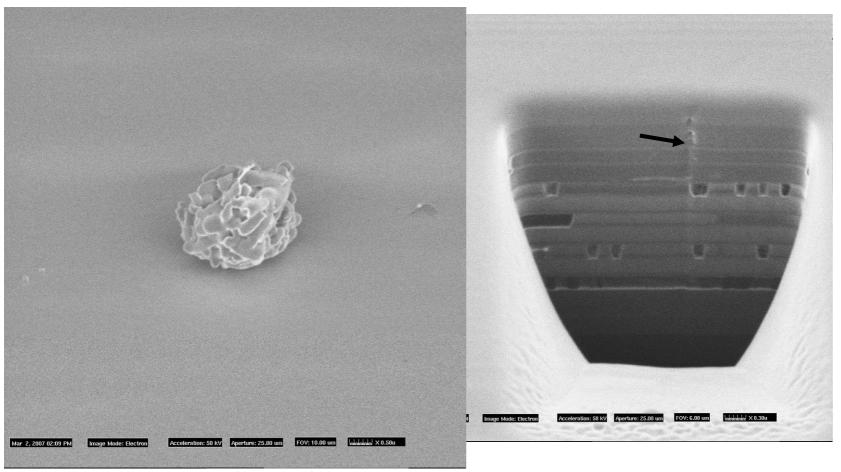
### ESDFOS on Cu-metallized devices (6)



No one would imagine this particle to be ESDFOS-caused

...but the FIB cross section proves exactly this (180° rotated cut thru hole)

### ESDFOS on Cu-metallized devices (8)



In some cases, ESDFOS is accompagnied by small, "collected-material"- particles, which disappear after the FIB cross section

# Conclusions for Charge Generation: Where Do We Have ESD-Risks?

- Touching or disconnecting isolating materials
- Rolling movements of isolating materials
- Fast movement of DI-water, powders, sand etc....
- Mechanical friction

Usually it is sufficient, if one of the participating materials is an isolator

# Tool ESD Risk Assessment Preparations

- Measurement of humidity and temperature
- Electrostatic activity measurement by an electrophorous: spark length should be 5mm or more vs GND.
- Measurement of the air ionization degree (in prep)
- Should the electrophorous test indicate insufficient electrostatic activity, the audit cannot be made.

# Visual check of material selection/ setup/ media

- Where are triboelectric materials very close to DIPs (devices in process)
- Triboelectric medis involved in process sequence? (DI-water w/o CO2-bubbling, gas flows, non-antistatic plexiglass-covers etc...)
- Are toothbelts, transmission/ transportation belts etc made from dissipative materials?
- Setups existing, which remember to electrostatic generators?

# Charge separation by water spraying in wafer sawing





Using a new developed Trek measurement head for humid environment measurements, it was found, that the surface voltage of water drops may reach some hundreds of volts

### **How to Fight Against Tool-ESDFOS?**

- Performing of a ("smooth") potential discharge (using copper GND belts etc)
- Use of antistatic or conductive materials
- Local discharging using ionizers
- Employee's training
- Chip-design-specific measures for deviceinternal soft discharge
- Periodical ESD checks of process equipment using suitable measurement setups

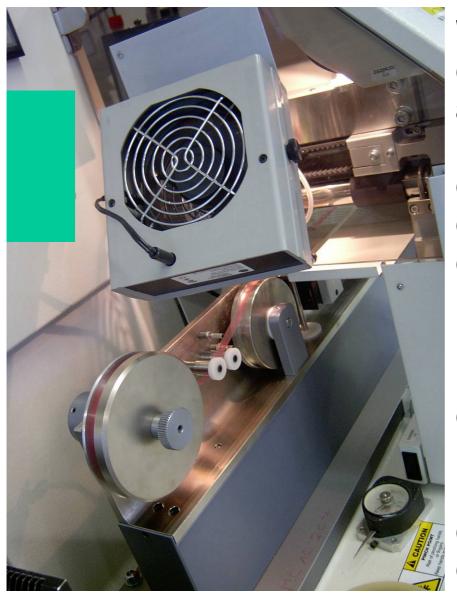
# Charge measurements at critical positions

- Robitics must be programmed/ supervised by the tool engineer
- Make measurements if possible during movements; use field meter or Trek voltmeter.
- Charging > 300 Volt is critical to ESDFOS. In case of bad electrostatic conditions (Elektrophorous <5mm) at least 100% safety margin should be added to the results. Breakdown of usual oxinitride passivation is at about 500V

#### Ionizer check

- Use charged-plate measurement setup
- If not available, use a charged metal ball and measure its discharging after exposing to the ionizer
- Ionizer PWR-supply: is it directly wired to the process equipment or is it switched separately? – Risk of bewing switched-off when the process is running
- Periodic check at least quarterly

#### Protection of the chip placing onto the tape

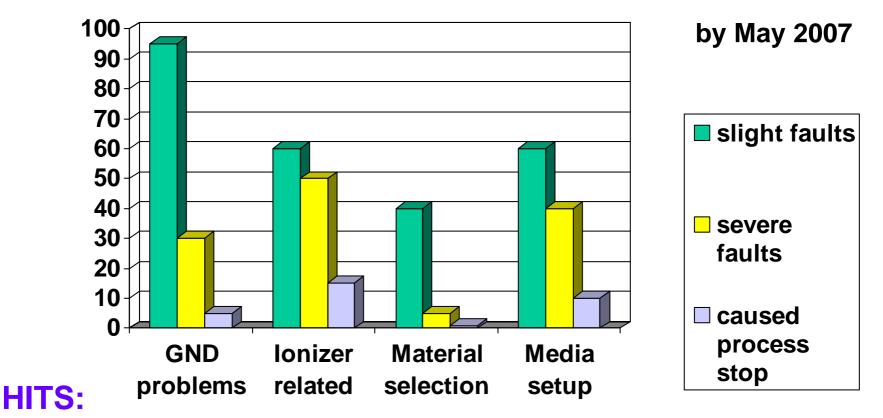


When electrostatic charging cannot be avoided, air ioniozers make the air locally conductive. This allows a controlled, smooth discharge of charged bodies and dies. However, mounting instructions must be carefully considered. The range and direction of an ionizer is very limited, depending from its construction

### GND connections/ resistances

- Visual check of process sequences
- Measurements of metallic parts to GND:
  Resistance should be < 1MOhm. Attention:
  No scratching with measurement needle:
  Lacquered or anodised surfaces are isolating and chargeable!</li>
- GND-concept (GND-star, defined potential, etc.)
- If necessary, scope measurements on critical pulses, coupled for example by internal RF or sparking (e.g. wireball-bonders)

#### Failures in assembly tools by Failure type



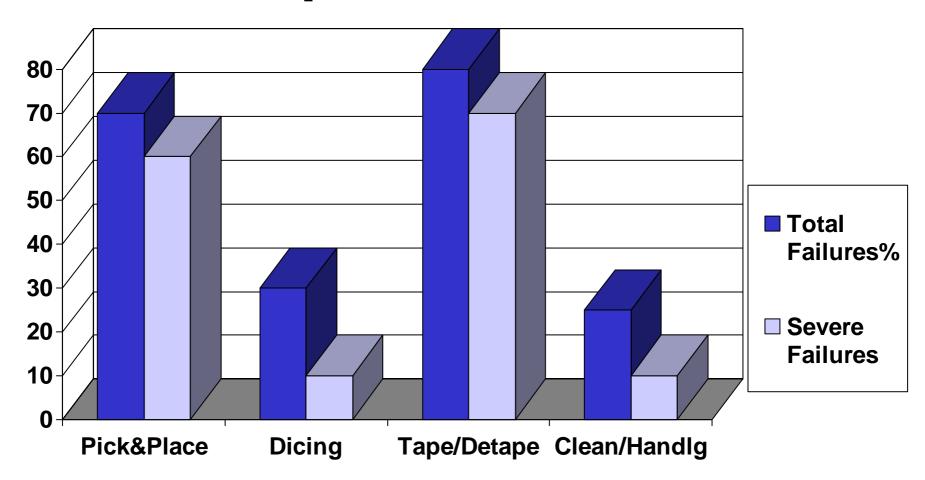
-GND: floating, anodised material, no GND concept, metal on plastics

-lonizer: missing, no function, out-of-range, inst.localisation; sw.off

-Material: Teflon rails and wheels, triboelectr. transmission-/tooth-belts

-Media/ Setup: foils/ carrier tapes, Water, gas/ airstreams

# Audit results by assembly processes



# Space availability for ESD protection

- Devices become more sensitive due to structure miniaturization
- Shrinking success must not be eaten by requesting more ESD protection

## **New thinking in ESDFOS**

- Process equipment needs to be ESD certified
- Should we approach to standardized or engineering solutions?
- Ban of triboelectric process media, especially taping foils

### ESD ideas entering into...

- System ESD protection
- Other branches (hospital, textile industry...) more and more involved
- Machine construction
- MEMS/ MOEMS (specific failure modes)

# High speed circuitry

- ESD pulses do not obey "what they should": HBM, CDM, MM are only virtual approaches; frequently, they don't match with field reality
- Reality requires new test strategies: VFTLP, PCB-CDM....? (Leadership of FhG-IZM)

### F/A Diagnosis on ESD-related problems

- ESD often masked by subsequent EOS
- ESDFOS specific to technologies
- Non-destructive ESD and ESDFOS problems (memory delete, reset etc)
- ESDFOS on power semiconductors, causing border passivation problems

# Conclusion: are our efforts in ESD protection on the right focus?

- ESD-protected workplace setup
- ESD robotic tool protection
- ESD-useful design
- ESD-test strategies
- Understand electrostatic activity
- System-ESD-protection
- Training/ Education
- ESD-related F/A diagnosis

Today's focus	Future need
++	$\downarrow$
0	<b>↑</b>
+	<b>↑</b>
+	<b>↑</b>
	<b>↑</b>
	<b>↑</b>
+	$\rightarrow$
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